

Date	User	Film	Recipe	Substrate T	Coat time	Dep.time	Thickness	JAW EC-400 (Woolam S.E.)			Index -1%	Dep.rate	Avg.dep. rate			HF e.r.	Stress	Avg Stress	Avg+10%	Avg-10%	LPD (light point defects)		Comment	MIKE SIIVA	
								Index @632.8nm	Index @1550nm	Index @632.8nm			(nm/min)	(nm/min)	(nm/min)						(nm/min)	(nm/min)			before dep.
<b>Oxide</b>																									
01/17/14	Bijana	SiO2	Oxide	300	10min	600.00	2855.83	1.472	1.461	1.472	1.487	1.458	28.56	27.99	28.83	27.15	493.56	-281.41	-270.15	-297.16	-243.13	166	329	Uniform film	
01/29/14	Bijana	SiO2	Oxide	300	10min	600.00	2762.42	1.474	1.463	1.472	1.487	1.458	27.62	27.99	28.83	27.15		-270.15	-297.16	-243.13			Uniform film		
02/03/14	Bijana	SiO2	Oxide	300	10min	600.00	2772.81	1.473	1.462	1.472	1.487	1.458	27.73	27.99	28.83	27.15	576.43	-262.42	-270.15	-297.16	-243.13	116	285	Uniform film	
02/18/14	Bijana	SiO2	Oxide	300	10min	600.00	2772.60	1.473	1.462	1.472	1.487	1.458	27.73	27.99	28.83	27.15	574.32	-265.31	-270.15	-297.16	-243.13	29	137	Uniform film	
03/12/14	Bijana	SiO2	Oxide	300	10min	600.00	2776.83	1.473	1.462	1.472	1.487	1.458	27.77	27.99	28.83	27.15	544.14	-283.68	-270.15	-297.16	-243.13	87	115	Uniform film	
04/03/14	Bijana	SiO2	Oxide	300	10min	600.00	2855.11	1.470	1.461	1.472	1.487	1.458	28.55	27.99	28.83	27.15	662.42	-257.91	-270.15	-297.16	-243.13	92	111	Uniform film	

Avg Thickness	2799.27	Avg HF e.r.	570.17
Avg Index	1.472	Avg Stress	-270.15
Index+1%	1.487	Avg+10%	-297.16
Index-1%	1.458	Avg-10%	-243.13
Avg.dep.rate	27.99		
Avg+3%	28.83		
Avg-3%	27.15		

